



US006648503B2

(12) **United States Patent**
Tanaka et al.

(10) **Patent No.:** US 6,648,503 B2
(45) **Date of Patent:** Nov. 18, 2003

(54) **CALORIMETER AND MANUFACTURING METHOD THEREOF**

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(*) Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 0 days.

(21) Appl. No.: 09/760,030

(22) Filed: Jan. 12, 2001

(65) **Prior Publication Data**

US 2002/0003830 A1 Jan. 10, 2002

(30) **Foreign Application Priority Data**

Jan. 14, 2000 (JP) 2000-006509
Dec. 25, 2000 (JP) 2000-393134

(51) **Int. Cl.⁷** G01K 17/02; G01N 7/02;
G01N 25/00; G01J 5/20

(52) **U.S. Cl.** 374/31; 374/10; 250/338.1;
422/51

(58) **Field of Search** 374/31, 41, 42,
374/121, 10, 32; 422/51; 250/338.1, 338.4,
332; 29/592

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(57) **ABSTRACT**

A colorimeter has an absorber for absorbing radiation energy and converting the radiation energy into thermal energy. A resistor is connected to the absorber for converting thermal energy into an electrical signal. A membrane is connected to the resistor for controlling a thermal discharge from the resistor. A substrate is connected to the membrane and has a tri-layer structure comprised of an etching layer having a preselected thickness, an etching stop layer and a support substrate. The membrane is spaced-apart from a main surface of the etching stop layer by the preselected thickness of the etching layer.

9 Claims, 11 Drawing Sheets

